L Number	Hits	Search Text	DB	Time stamp
1	4416	ion adj beam adj etch\$3	USPAT;	2004/02/27 10:53
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM TDB	
2	472	(ion adj beam adj etch\$3) and focus\$3 near	USPAT;	2004/02/27 12:10
2	1,2	ion adj beam	US-PGPUB;	
		Ton day beam	EPO; JPO;	
			DERWENT;	
			IBM TDB	
3	128	((ion adj beam adj etch\$3) and focus\$3 near	USPAT;	2004/02/27 10:55
	120	ion adj beam) and (etch\$3 remov\$3 strip\$4)	US-PGPUB;	2004/02/27 10:33
			1	
		near (resist photoresist organic metal\$3	EPO; JPO;	
		conduct\$3)	DERWENT;	
		/// 21 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2	IBM_TDB	0000100100 10 55
4	92	((ion adj beam adj etch\$3) and focus\$3 near	USPAT;	2004/02/27 10:56
		ion adj beam) and (etch\$3 remov\$3 strip\$4)	US-PGPUB;	
		adj (resist photoresist organic metal\$3	EPO; JPO;	
		conduct\$3)	DERWENT;	
			IBM_TDB	
5	22	(((ion adj beam adj etch\$3) and focus\$3 near	USPAT;	2004/02/27 10:56
		ion adj beam) and (etch\$3 remov\$3 strip\$4)	US-PGPUB;	
		adj (resist photoresist organic metal\$3	EPO; JPO;	
		conduct\$3)) and (etch\$3 remov\$3 strip\$4) adj	DERWENT;	
		(resist photoresist organic metal\$3	IBM_TDB	
		conduct\$3) with beam		
6	1687	(ion adj beam adj etch\$3) and focus\$3 near	USPAT;	2004/02/27 12:12
		ion adj beam FIB and etch\$3	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM TDB	
7	1243	((focus\$3 near ion near beam) FIB) with	USPAT;	2004/02/27 12:13
		etch\$3	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM TDB	
8	3	((focus\$3 near ion near beam) FIB) with	USPAT;	2004/02/27 12:18
	-	etch\$3 same organic adj (film layer)	US-PGPUB;	
		coonty bame organize and (rrrm rayer)	EPO; JPO;	
			DERWENT;	
		·	IBM TDB	
9	0	20010027029.URPN.	USPAT	2004/02/27 12:17
10	3	((focus\$3 near ion near beam) FIB) same	USPAT;	2004/02/27 12:17
	3	etch\$3 same organic adj (film layer)not	US-PGPUB;	2001,02,27 12.20
		(((focus\$3 near ion near beam) FIB) with	EPO; JPO;	
		etch\$3 same organic adj (film layer))	DERWENT;	
		ecchips same organic adj (111m rayer)	IBM TDB	1
11	26	((focus\$3 near ion near beam) FIB) same	USPAT;	2004/02/27 12:42
11	20	etch\$3 and organic adj (film layer) not	US-PGPUB;	2004/02/2/ 12:42
ł			1	1.
İ		((((focus\$3 near ion near beam) FIB) with	EPO; JPO;	
		etch\$3 same organic adj (film layer))	DERWENT;	
		(((focus\$3 near ion near beam) FIB) same	IBM_TDB	
		etch\$3 same organic adj (film layer)not		
		(((focus\$3 near ion near beam) FIB) with		
	_	etch\$3 same organic adj (film layer))))		
12	20	((focus\$3 near ion near beam) FIB) and	USPAT;	2004/02/27 12:42
		conduct\$4 near organic	US-PGPUB;	
			EPO; JPO;	1 .
			DERWENT;	
			IBM TDB	